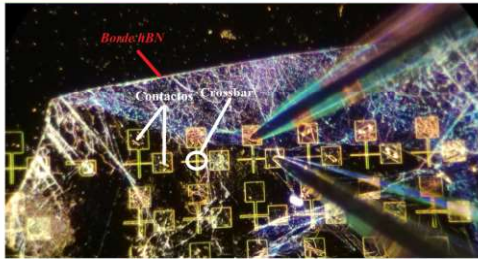




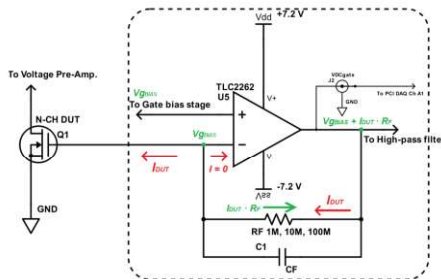
Motivation

- Hexagonal boron nitride (*h*-BN) is an attractive candidate as insulator for 2D materials based nano-electronics due to its excellent electrical, thermal, optical and mechanical properties.[1]
- Thanks to resistive switching behavior present in chemical vapor deposited (CVD) *h*-BN sheets, the fabrication of synapses in the form of cross-bar devices potentially enables the large scale integration of neuromorphic circuits based on 2D materials. [2]
- Low frequency noise current is widely accepted as a defect-related mechanism in thin films and appears as both a threat and an opportunity in cross-bar applications [3], hence its analysis is of utmost importance at both the materials and device levels.

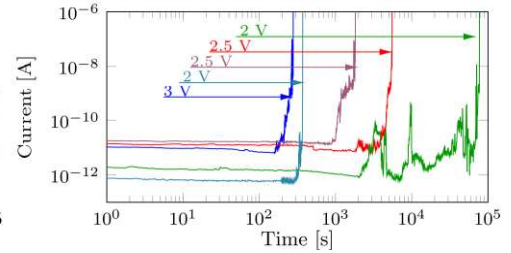
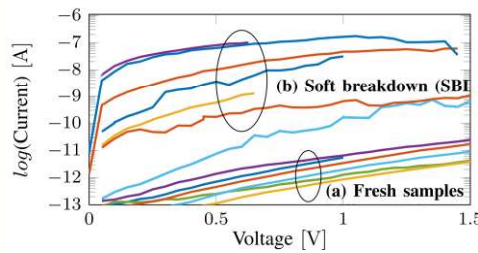
Experimental



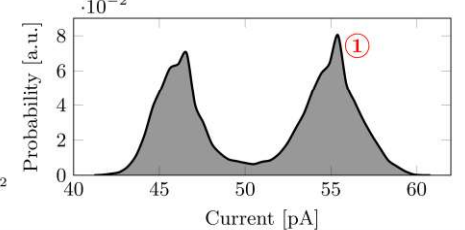
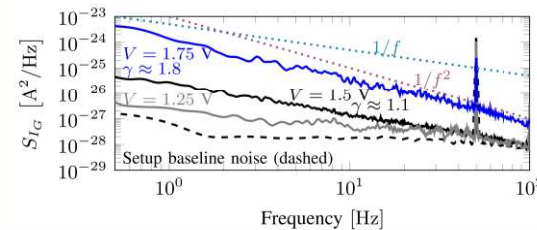
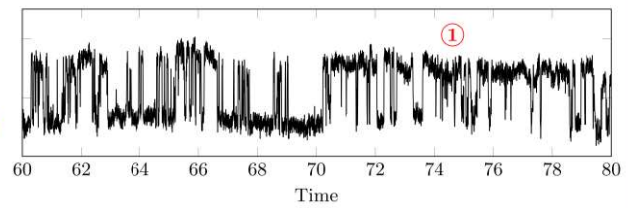
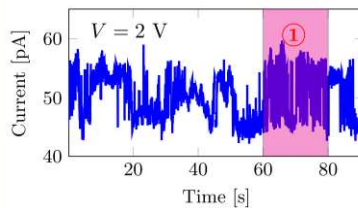
- 5 $\mu\text{m} \times 5 \mu\text{m}$ Au/multilayer *h*-BN/Au cross bar devices, courtesy of LanzaLab.
- h*-BN films deposited via CVD between conformed electrodes (see wrinkles and boundaries)[4].
- DC measurements performed with SMU. Low frequency noise measured using a calibrated, custom, low-noise transimpedance amplifier (TIA) @ 10^8 V/A , 100 Hz BW.



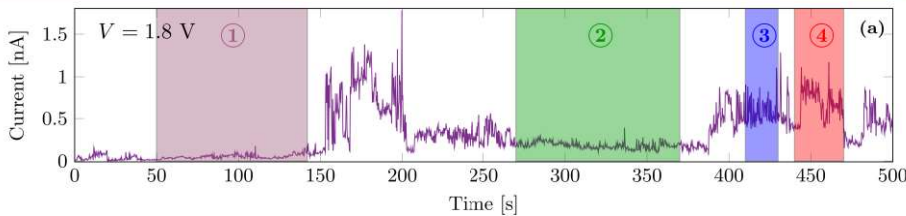
Measurement Results



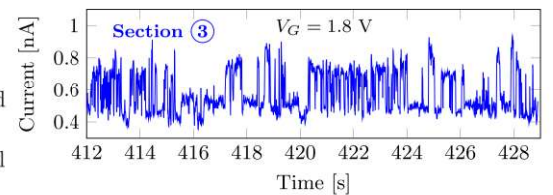
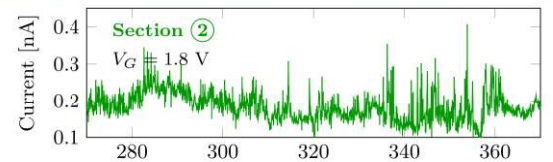
- I-V and I-t measurements show good agreement with the literature for similar devices, showing different conduction levels and a progressive current increase under constant voltage stress.
- Pristine (fresh) devices showed $1/f$ (flicker) noise at voltages up to 1.75 V.
- Random telegraph noise (RTN) appeared in the range 1.75V~2V with clear two-level sections in acquisitions as long as 5 minutes. Similar to behavior in CAFM experiments.[5]



RTN vs. flicker noise competition under soft breakdown (SBD)



- Under SBD, current is highly unstable at constant voltage (volatile switching regime).
- Different sections show competition between $1/f$ and RTN behavior. This can be linked to the presence of point-defects near the main conduction path.
- Results are important for the application of cross-bars in complex circuits, such as neural networks, physically unclonable functions or random number generators.



Conclusions

- At low currents ($< 1 \mu\text{A}$), noise in Au/*h*-BN/Au cross-bars can be ascribed to the presence of (most likely) boron vacancies diffusing across the insulator.
- In pristine devices, RTN-like signals are present in the 1.75V~2V range, while noise is mostly flicker at lower voltages.
- Migration of boron vacancies in the vicinity of stress induced conduction paths through the dielectric result in the competition of flicker vs. RTN noise under constant voltage.

References

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- [2] Y. Shi, *Nat. Elect.*, 1(8), 2018.
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- [4] X. Liang, *EDTM 2019*, 258-260.
- [5] A. Ranjan, *App. Phys. Lett.*, 112(13), 2018.